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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/772,945	02/04/2004	Peter J. Fricke	200310842-1	5316
22879	7590	10/11/2007		
HEWLETT PACKARD COMPANY P O BOX 272400, 3404 E. HARMONY ROAD INTELLECTUAL PROPERTY ADMINISTRATION FORT COLLINS, CO 80527-2400			EXAMINER NADAV, ORI	
			ART UNIT	PAPER NUMBER
			2811	
			MAIL DATE	DELIVERY MODE
			10/11/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary

Application No.

10/772,945

Applicant(s)

FRICKE ET AL.

Examiner

Ori Nadav

Art Unit

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-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 18 September 2007.
- 2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-6, 8-33 and 36-59 is/are pending in the application.
- 4a) Of the above claim(s) 2, 12-15, 17-25, 36, 37, 42-46 and 50-54 is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1, 3-6, 8-11, 16, 26-33, 38-41, 47-49 and 55-59 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
- ☐ Certified copies of the priority documents have been received.
 - ☐ Certified copies of the priority documents have been received in Application No. _____.
 - ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- ☐ Notice of References Cited (PTO-892)
- ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- ☐ Information Disclosure Statement(s) (PTO/SB/08)
Paper No(s)/Mail Date _____
- ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____
- ☐ Notice of Informal Patent Application
- ☐ Other: _____

DETAILED ACTION

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claim 5 is rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. There is no support in the specification for a device comprising a control element comprising two tunnel junctions, as recited in claim 5.

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 1, 3-6, 8-11, 16, 26-33, 38-41, 47-49 and 55-59 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

The claimed limitations of a second conductive layer being at least partially aligned with the middle electrode, as recited in claims 47 and 55, and memory cells of each set being at least partially aligned vertically with each other, as recited in claim 30,

are unclear as to whether the second conductive layer is aligned or not aligned with the middle electrode, and how two elements can be partially aligned.

The claimed limitation of "memory cell further comprises a tunnel junction", as recited in dependent claim 5, is unclear as to whether said tunnel junction is the same element recited in independent claim 1, or a different element.

The claimed limitations of "each control element including a tunnel junction and a silicon-rich oxide insulator configured to inject current into the tunnel junction when the memory cell is selected", as recited in claims 1, 16, 26, 38, 47 and 55, are unclear as to which element is configured to inject current into the tunnel junction when the memory cell is selected.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 1, 3-6, 8-11, 16, 26-33, 38-41, 47-49 and 55-59, as best understood, are rejected under 35 U.S.C. 103(a) as being unpatentable over Miyasaka (4,476,547) in view of Udayakumar et al. (2005/0012126).

Miyasaka teaches in figure 5 and related text a memory array comprising:

a) a multiplicity of row conductors WL and a multiplicity of column conductors BL, the row conductors and column conductors being arranged to cross at cross-points, and
b) a memory cell C disposed at each cross-point, each memory cell having exactly two terminals and having a storage element and a control element coupled in series between a row conductor and a column conductor (column 1, lines 63-67).

Miyasaka does not teach that each control element including a tunnel junction and a silicon-rich oxide insulator.

Udayakumar et al. teach in figure 7F and related text a memory cell Cfe having exactly two terminals and having a storage element and a control element wherein the control element including a tunnel junction and a silicon-rich oxide insulator SILOX2.

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to use a tunnel junction and a silicon-rich oxide insulator in each control element of Miyasaka's device in order to make an operable device and in order to improve the characteristics of the device, respectively. The combination is motivated by the teachings of Udayakumar et al., who points out the advantages of using a silicon-rich oxide insulator.

Regarding the claimed limitations of "each control element including a tunnel junction and a silicon-rich oxide insulator configured to inject current into the tunnel junction when the memory cell is selected", these features are inherent in prior art's device, because prior art's structure is identical to the claimed structure. Note that a recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably

distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim.

Regarding claim 4, prior art's device includes the silicon-rich insulator of each memory cell is electrically isolated from the silicon-rich insulators of all other memory cells.

Regarding claims 5-6 and 8-10, it would have been obvious to a person of ordinary skill in the art at the time the invention was made to use a control element of each memory cell comprises a tunnel junction, and the storage element of each memory cell comprises an anti-fuse, a fuse, a tunnel junction, a state-change layer, a chalcogenide, in prior art's device in order to use known memory control and storage elements, of which official notice is taken.

Regarding claim 11, Miyasaka teaches in figure 5 and related text a row conductors are arranged in mutually orthogonal relationship with the column conductors.

Regarding claim 16, prior art's device includes a memory cell disposed at each cross-point, each memory cell comprising means for storing data and means for controlling the means for storing data, the means for storing data and means for controlling being coupled in series between a row conductor and a column conductor, and each means for controlling including a silicon-rich insulator.

Regarding claim 26, prior art's device includes a tunnel-junction layer SiN over the silicon rich insulator and a second conductive layer 128 over the tunnel-junction layer.

Prior art does not state that the memory cell is formed by a method of

b) depositing and patterning a first conductive layer over the substrate, and

c) forming and patterning a second conductive layer,

However, these process limitations would not carry patentable weight in this claim drawn to a structure, because distinct structure is not necessarily produced.

Note that a "product by process" claim is directed to the product per se, no matter how actually made, *In re Hirao*, 190 USPQ 15 at 17 (footnote 3). See also *In re Brown*, 173 USPQ 685; *In re Luck*, 177 USPQ 523; *In re Fessmann*, 180 USPQ 324; *In re Avery*, 186 USPQ 161; *In re Wertheim*, 191 USPQ 90 (209 USPQ 554 does not deal with this issue); and *In re Marosi et al.*, 218 USPQ 289, all of which make it clear that it is the patentability of the final product per se which must be determined in a "product by process" claim, and not the patentability of the process, and that an old or obvious product produced by a new method is not patentable as a product, whether claimed in "product by process" claims or not. Note that the applicant has the burden of proof in such cases, as the above case law makes clear.

Regarding claim 38, prior art's device includes a first interlayer dielectric over the storage layer (122 in Udayakumar et al., figure 7F), and having an opening through the first interlayer dielectric and extending to the storage layer, and having a conductive

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material therein as a middle electrode 124, this conductive layer is contiguous with the storage layer.

Prior art does not state that the memory cell is formed by a method of

- b) depositing and patterning a first conductive layer over the substrate, and
- c) forming and patterning a second conductive layer,
- d) forming and patterning first and second interlayer dielectrics over the storage layer,
- e) forming an opening through the first interlayer dielectric and extending to the storage layer,
- g) filling the opening through the first interlayer dielectric with conductive material to form a middle electrode.

However, these process limitations would not carry patentable weight in this claim drawn to a structure, because distinct structure is not necessarily produced.

Regarding claims 30, 47 and 55, prior art's device includes a second interlayer dielectric (126 in Udayakumar et al., figure 7F), is formed over the storage layer, forming vias as required through the second interlayer dielectric to selectively interconnect memory cells of the memory arrays.

Prior art does not state that the memory cell is formed by a method of

- b) depositing and patterning a first conductive layer over the substrate, and
- c) forming and patterning a second conductive layer,
- d) forming and patterning first and second interlayer dielectrics over the storage layer,

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e) forming an opening through the first interlayer dielectric and extending to the storage layer,

g) filling the opening through the first interlayer dielectric with conductive material to form a middle electrode.

k) forming vias as required through the second interlayer dielectric, and repeating steps

b) through k) until a desired number of memory array layers have been formed.

However, these process limitations would not carry patentable weight in this claim drawn to a structure, because distinct structure is not necessarily produced.

Regarding claims 27-29, 31-33, 39-41, 48-49 and 56-57, Miyasaka teaches a memory array comprising a multiplicity of the memory cells, a substrate carrying electronics and an IC comprising a multilayer memory, wherein a multiplicity of the memory arrays are arranged in memory layers.

Regarding claims 58-59, Miyasaka teaches in figure 5 and related text the two terminals of the two terminal memory cell disposed at each cross-point comprise the row conductor and column conductor respectively.

Response to Arguments

Applicant argues that the claimed limitations of a second conductive layer being at least partially aligned with the middle electrode, as recited in claims 47 and 55, and

memory cells of each set being at least partially aligned vertically with each other, as recited in claim 30, are clear because "partially aligned" means that some portion of the first structure overlaps some portion of the second structure.

The term "align" is defined as "to bring in a line". That is, the edges of both structures are "brought in line". The term "overlap" means "to extend over". That is, some portion of one element extends over some portion of the second element. If two elements overlap each other, they are not necessarily aligned with each other.

Note that applicant did not recite that specific portion of the first structure is aligned with a specific portion of the second structure.

Applicant argues that the combination is not motivated by the teachings of Miyasaka, because Miyasaka does not teach using a silicon-rich oxide insulator.

The examiner agrees that Miyasaka does not teach using a silicon-rich oxide insulator. Udayakumar et al. teach using a silicon-rich oxide insulator. The combination is motivated by the teachings of Udayakumar et al., who points out the advantages of using a silicon-rich oxide insulator.

Applicant argues that a proper *prima facie* case of obviousness has not been made, because the "teachings by Udayakumar et al. also do not suggest the use of silicon-rich oxide in a combination with the control element of Miyasaka. Udayakumar et al. does not even mention a control element", and "The silicon-rich oxide of Udayakumar et al. is in a different structure, for a different purpose, with a different

result from applicants' invention". Applicant further argues that "In any combination of the teachings of the two references, the silicon-rich silicon oxide of Udayakumar et al. would not be part of any control element".

Miyasaka teaches in figure 5 and related text a control element being a capacitor, coupled in series between a row conductor and a column conductor (column 1, lines 63-67). Udayakumar et al. teach in figure 7F and related text a capacitor structure comprising a silicon-rich oxide insulator SILOX2. It is unclear to the examiner why an artisan would not be motivated to use the superior capacitor structure of Udayakumar et al. in Miyasaka's device, in particular when Udayakumar et al. points out the advantages of said structure.

Note that forming Udayakumar et al.'s capacitor in Miyasaka's device, would result in a device comprising a memory array comprising:

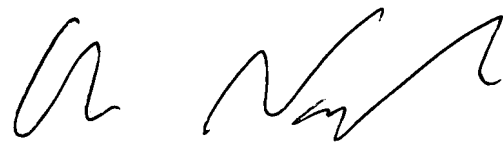
a) a multiplicity of row conductors and a multiplicity of column conductors, the row conductors and column conductors being arranged to cross at cross-points, and

b) a memory cell disposed at each cross-point, each memory cell having exactly two terminals and having a storage element and a control element coupled in series between a row conductor and a column conductor and each control element including a silicon-rich oxide insulator, as claimed.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ori Nadav whose telephone number is 571-272-1660. The examiner can normally be reached between the hours of 7 AM to 4 PM (Eastern Standard Time) Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Lynne Gurley can be reached on 571-272-4670. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



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